

EAST Search History

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|--|---|------------------|---------|------------------|
| L13 | 78 | 257/E21.224.ccls. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/04/11 10:05 |
| L12 | 140 | 134/33.ccls. and (clean\$4 or etch\$4 or remov\$4 or polish\$4 or grind\$4) near4 (edge or bevel or bead) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/04/11 10:05 |
| L11 | 859 | 134/33.ccls. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/04/11 09:44 |
| L10 | 385 | 134/9.ccls. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/04/11 09:44 |
| L3 | 120 | 438/694.ccls. and (clean\$4 or etch\$4 or remov\$4 or polish\$4 or grind\$4) near4 (edge or bevel or bead) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/04/11 09:44 |
| L9 | 205 | 438/748.ccls. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/04/11 09:16 |
| L4 | 213 | 438/747.ccls. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/04/11 09:02 |

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|-----|------|---|---|----|----|------------------|
| S38 | 15 | (US-20030041879-\$ or US-20050087441-\$ or US-20050079713-\$ or US-20010052159-\$ or US-20030116444-\$).did. or (US-5128281-\$ or US-6537416-\$ or US-5176783-\$ or US-6070284-\$ or US-5608943-\$ or US-6797074-\$ or US-6063232-\$ or US-5868857-\$ or US-6550091-\$ or US-6615854-\$).did. | US-PGPUB; USPAT | OR | ON | 2006/04/11 08:58 |
| L6 | 18 | ("4968375").URPN. | USPAT | OR | ON | 2006/04/11 08:54 |
| S20 | 42 | 438/694.ccor. and (clean\$4 or etch\$4 or remov\$4 or polish\$4 or grind\$4) near4 (edge or bevel or bead) | US-PGPUB; USPAT | OR | ON | 2006/04/11 08:40 |
| S1 | 3275 | (metal or metallic or copper or cu) near5 (edge or bevel or bead) near6 (etch\$4 or remov\$4) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/04/11 08:40 |
| L1 | 3844 | 438/694.ccls. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/04/11 08:40 |
| S39 | 584 | 438/690.ccls. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/04/10 17:12 |
| S37 | 19 | (metal or metallic or copper or cu) near6 (edge or bevel) near6 (etch\$4 or remov\$4 or clean\$4) and (bead or meniscus or pool or receptacle) near3 (etch or etchant or etching or acid or acidic) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/04/10 16:55 |
| S36 | 11 | (electroplat\$4 or electro-plat\$4) near5 (metal or metallic or copper or cu) and (metal or metallic or copper or cu) near5 (edge or bevel) near6 (etch\$4 or remov\$4) and (acid or etchant or etching or etch) near3 (bead\$3) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/04/10 16:51 |
| S35 | 218 | edge near bead near (remov\$4) and (cavity or opening or trench or groove or aperture or grooved or contour) near8 (substrate or workpiece or wafer) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/04/10 16:18 |

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|-----|------|--|---|----|----|------------------|
| S34 | 700 | edge near bead near (remov\$4) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/04/10 16:18 |
| S33 | 10 | (groove or trench or cavity or opening) near6 (etchant or etching or removing or removal) near6 (bead or surface near tension) same (wafer or substrate or workpiece) near4 (edge or side or bevel or end or outer or outside) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/04/10 16:17 |
| S32 | 340 | (groove or trench or cavity or opening) near6 (etchant or etching or removing or removal) near5 (edge or bevel) near6 (wafer or substrate or workpiece) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/04/10 16:14 |
| S31 | 6 | ("5865984" "6056869" "6309981" "6352623" "6610190" "6615854"). PN. | US-PGPUB; USPAT; USOCR | OR | ON | 2006/04/10 15:42 |
| S30 | 444 | (substrate or wafer) near2 (edge or bevel) near5 (etch\$4 or remov\$4 or scrub\$4) and (cavity or recess or recessed or opening) near4 (etchant or acid or etching or acidic or solution) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/04/10 13:43 |
| S29 | 3323 | (substrate or wafer) near2 (edge or bevel) near3 (etch\$4 or remov\$4 or scrub\$4) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/04/10 13:42 |
| S28 | 117 | (substrate or wafer) near5 (edge or bevel or bead) near5 (etch\$4 or remov\$4) and (acid or etchant or etching or fluid) near4 bead | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/04/10 13:41 |

Interference Search

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| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|---|----------|------------------|---------|------------------|
| L14 | 6 | ((edge or bevel or circumference or circumferential or end) near4 (wafer or substrate or workpiece) and (etchant or etching or cleaning or cleansing or cleaner or acid) near4 (bead or surface near tension)).clm. | US-PGPUB | OR | ON | 2006/04/11 10:16 |
| L16 | 56 | ((edge or bevel or circumference or circumferential or end) near4 (wafer or substrate or workpiece) near6 (clean\$4 or removal or removing or etching or etched) near10 (metal or conductive or photoresist or resist)).clm. | US-PGPUB | OR | ON | 2006/04/11 10:20 |
| L17 | 41 | ((groove or grooved or trench or opening or recess or cavity) near6 (etchant or fluid or acid or cleanser or cleaner or cleaning or etching) near6 (bead or meniscus or surface near tension)).clm. | US-PGPUB | OR | ON | 2006/04/11 10:27 |
| L18 | 10 | ((groove or grooved or trench or opening or recess or cavity) near6 (etchant or fluid or acid or cleanser or cleaner or cleaning or etching) near6 (bead or meniscus or surface near tension) and (wafer or substrate or workpiece)).clm. | US-PGPUB | OR | ON | 2006/04/11 10:27 |
| L19 | 3 | ((groove or grooved or trench or opening or recess or cavity) near6 (mated or mating or conforming or holding or conformal or conformed) near4 (edge or circumference or circumferential or curvature or bevel) and (edge or circumference or bevel or outer or end) near3 (clean\$3 or etch\$4)).clm. | US-PGPUB | OR | ON | 2006/04/11 10:29 |
| L20 | 32 | ((groove or grooved or trench or opening or recess or cavity) and (semiconductor or wafer or workpiece) and (clean\$3 or etch\$4 or remov\$4 near (material or metal or conductive or photoresist or resist)) and (bead or meniscus or tension) and (motion or moving or rotation or rotating or rotated or rpm or sliding)).clm. | US-PGPUB | OR | ON | 2006/04/11 10:31 |